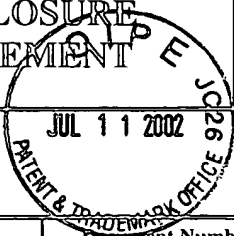


INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 278.00060120	Serial No.: 10/003,224
	Applicant(s): Larson et al.	Confirmation No.: 5031
	Filing Date: October 26, 2001	Group: 2882



U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>CF</i>	3,766,381	10/16/73	Watson			
<i>CF</i>	3,772,522	11/13/73	Hammond et al.			
<i>CF</i>	4,048,498	09/13/77	Gerlach et al.			
<i>CF</i>	4,810,880	03/07/89	Gerlach			
<i>CF</i>	5,315,113	05/24/94	Larson et al.			
<i>CF</i>	5,990,476	11/23/99	Larson et al.			

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FOREIGN PATENT DOCUMENTS

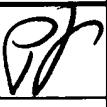

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	None						

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Document Description
<i>CF</i>	"Amicus: A High Speed Etching Source - Development and Application," [online]. Presented at AVS '99, the 46 th International Symposium, Seattle Wash., 1999 Oct. 26, [retrieved on 2001-10-05]. Retrieved from the Internet: <URL: http://www.kratos.com/EApps/Kaufmn.html >. (5 pgs.).
<i>CF</i>	Briggs et al., eds., <i>Practical Surface Analysis 2nd Ed., Vol. I</i> , "Auger and X-ray Photoelectron Spectroscopy," Sec 5.4.2, John Wiley & Sons, Ltd., Chichester 1995; cover page, title page and 244-248. (6 pgs.).
<i>CF</i>	Gibson et al., "Characterizing Nanometer Oxy-nitride Films with ESCA Low Energy Sputter Depth Profiles," Presented at 15 th International Vacuum Congress (IVC-15), AVS 48 th International Symposium (AVS-48), 11 th International Conference on Solid Surfaces (ICSS-11), October 28, 2001. Abst. (1 pg.).
<i>CF</i>	Moulder et al., "Ultra Shallow Depth Profiling by ESCA and SIMS," Presentation at National Symposium of American Vacuum Society (AVS), Baltimore, MD, Nov. 2-6 1998, 31 pgs.

EXAMINER <i>William A. Hunt</i>	Date Considered 1-8-03
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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Examiner Initial	Document Description
	"PHI Quantum 2000 Scanning ESCA Microprobe™," Product Information. Physical Electronics, Inc., 1999; (8 pgs.).
	Principe et al., "Pushing The Limits of Nitrogen Doped Silicon Oxide Gate Dielectric Materials: The Material Characterization Role of TEM/STEM, PEELS, and XPS" Presented at America Vacuum Society 48 th International Symposium, San Francisco, CA, 2001, Oct. 28- Nov. 25 th Abst. (24 pgs.).

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